

| Ref # | Hits | Search Query | DBs | Default Operator | Plurals | Time Stamp |
|-------|------|--|------------------------------|------------------|---------|------------------|
| L1 | 55 | electroless\$2 and capping layer same silane | US-PGPUB; USPAT; USOCR | ADJ | ON | 2006/01/19 12:46 |
| L2 | 1 | electroless\$2 and capping layer same silane same (cobalt or co) | US-PGPUB; USPAT; USOCR | ADJ | ON | 2006/01/19 12:47 |
| L3 | 29 | electroless\$2 and capping layer same silane and (cobalt or co) | US-PGPUB; USPAT; USOCR | ADJ | ON | 2006/01/19 12:50 |
| L4 | 2 | electroless\$2 and capping layer same silane and (cobalt) | US-PGPUB; USPAT; USOCR | ADJ | ON | 2006/01/19 12:59 |
| L5 | 0 | (plasma near2 chemical vapor deposition or pecvd) same capping layer same silane same cobalt | US-PGPUB; USPAT; USOCR | ADJ | ON | 2006/01/19 13:01 |
| L6 | 4 | (plasma near2 chemical vapor deposition or pecvd) same capping layer same silane and cobalt | US-PGPUB; USPAT; USOCR | ADJ | ON | 2006/01/19 13:01 |
| L7 | 8 | (plasma near2 chemical vapor deposition or pecvd) same capping layer and silane and cobalt | US-PGPUB; USPAT; USOCR | ADJ | ON | 2006/01/19 13:20 |
| L8 | 16 | capping layer same (silicon or silicide) same cobalt same (copper or Cu) | US-PGPUB; USPAT; USOCR | ADJ | ON | 2006/01/19 13:12 |
| L9 | 1 | 8 and silane | US-PGPUB; USPAT; USOCR | ADJ | ON | 2006/01/19 13:12 |
| L10 | 229 | (plasma near2 chemical vapor deposition or pecvd) same silane and cobalt | US-PGPUB; USPAT; USOCR | ADJ | ON | 2006/01/19 13:21 |
| L11 | 16 | (plasma near2 chemical vapor deposition or pecvd) same silane and cobalt and capping layer | US-PGPUB; USPAT; USOCR | ADJ | ON | 2006/01/19 13:21 |
| L12 | 15 | ("20020036143" "5420072" "5447887" "5674787" "5695810" "5783483" "5824599" "6023100" "6228770" "6274932" "6352917").PN. OR ("6573606").URPN. | US-PGPUB; USPAT; USOCR | ADJ | ON | 2006/01/19 13:26 |
| L13 | 15 | 12 and (chemical vapor deposition or cvd) | US-PGPUB; USPAT; USOCR | ADJ | ON | 2006/01/19 14:26 |
| L14 | 772 | (cobalt silicide or cosi) same (capping or barrier or passivation) | US-PGPUB; USPAT; USOCR | ADJ | ON | 2006/01/19 14:27 |

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| L15 | 99 | (cobalt silicide or cosi) same (capping or barrier or passivation) same (copper or cu) | US-PGPUB; USPAT; USOCR | ADJ | ON | 2006/01/19 14:28 |
| L16 | 15 | (cobalt silicide or cosi) same (capping or barrier or passivation) same (copper or cu) same (chemical vapor deposition or \$2cvd) | US-PGPUB; USPAT; USOCR | ADJ | ON | 2006/01/19 15:00 |
| L17 | 0 | "10749776" | US-PGPUB; USPAT; USOCR | ADJ | ON | 2006/01/19 15:00 |
| L18 | 0 | "10?749776" | US-PGPUB; USPAT; USOCR | ADJ | ON | 2006/01/19 15:00 |
| L19 | 1 | "10/749776" | US-PGPUB; USPAT; USOCR | ADJ | ON | 2006/01/19 15:21 |
| L20 | 1 | "5695810".pn. | US-PGPUB; USPAT; USOCR | ADJ | ON | 2006/01/19 15:21 |
| S1 | 354 | electroless\$2 same refractory and (carbon silicon or nitrogen or C or Si or N) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2006/01/18 16:15 |
| S2 | 62 | electroless\$2 same refractory same (carbon silicon or nitrogen or C or Si or N) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2006/01/18 16:16 |
| S3 | 207 | S1 and (chemical vapor deposition or \$2cvd) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2006/01/18 16:16 |
| S4 | 30 | S2 and (chemical vapor deposition or \$2cvd) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2006/01/18 16:16 |
| S5 | 6 | ("20020084529" "20030176049" "5380560" "5695810" "5824599" "6197364").PN. | US-PGPUB; USPAT; USOCR | ADJ | ON | 2006/01/19 12:45 |